

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1-13. (Canceled)

14. (Currently Amended) An exposure apparatus ~~which exposes a substrate by radiating an exposure light beam onto the substrate through a liquid, the exposure apparatus~~ comprising:

a projection optical ~~system;~~ system from which an exposure light is radiated onto a substrate through a liquid to expose the substrate;

a liquid supply ~~mechanism- system~~ which supplies the liquid;

a liquid recovery ~~mechanism- system~~ which recovers the liquid; and

a substrate stage which holds the substrate, wherein:

a magnitude of a velocity of movement of the substrate stage differs depending on a distance between a first position and a second position when the substrate stage is moved substantially linearly from the first position to the second position in a state in which a liquid immersion area is locally formed on the substrate stage by using the liquid supply ~~mechanism system~~ and the liquid recovery ~~mechanism- system~~.

15. (Currently Amended) The exposure apparatus according to claim 14, when the magnitude of the velocity of movement of the substrate stage is decreased when the distance between the first position and the second position is not less than a predetermined amount as compared with when the distance between the first position and the second position is shorter than the predetermined amount.

16. (Currently Amended) An exposure apparatus ~~which exposes a substrate by radiating an exposure light beam onto the substrate through a liquid, the exposure apparatus~~ comprising:

~~a projection optical system; system from which an exposure light is radiated onto a~~  
substrate through a liquid to expose the substrate;

~~a liquid supply mechanism system~~ which supplies the liquid;

~~a liquid recovery mechanism system~~ which recovers the liquid; and

a substrate stage which holds the substrate, wherein:

a magnitude of a velocity of movement of the substrate stage differs depending on a direction of movement of the substrate stage from a first position to a second position when the substrate stage is moved substantially linearly from the first position to the second position in a state in which a liquid immersion area is locally formed on the substrate stage by using the liquid supply mechanism system and the liquid recovery mechanism system.

17. (Currently Amended) The exposure apparatus according to claim 16, wherein the magnitude of the velocity of movement of the substrate stage is decreased when the substrate stage is moved in a predetermined direction ~~in which a liquid recovery force brought about by the liquid recovery mechanism is smaller than~~ as compared with when the substrate stage is moved in a direction different from the predetermined direction.

18. (Currently Amended) The exposure apparatus according to claim 17, wherein ~~the no liquid recovery port of the liquid recovery mechanism is absent~~ system is arranged at a side of a space under the projection system in the predetermined ~~direction in which the liquid recovery force brought about by the liquid recovery mechanism is weak.~~ direction.

19-38. (Canceled)

39. (Currently Amended) An exposure method ~~for exposing a substrate by radiating an exposure light beam onto the substrate through a liquid, the exposure method~~ comprising:

~~exposing the substrate by radiating the~~ a substrate by radiating an exposure light beam onto the substrate through the liquid; a liquid;

moving the substrate from a first position to a second position while retaining the liquid on the substrate ~~when the substrate is unexposed; and~~ substrate; and

adjusting a magnitude of a velocity of movement of the substrate from the first position to the second position depending on a positional relationship between the first position and the second position.

40. (Currently Amended) The exposure method according to claim 39, wherein the magnitude of the velocity of movement of the substrate is decreased when a distance of the movement is not less than a predetermined distance as compared with when the distance of the movement is less than the predetermined distance.

41. (Currently Amended) The exposure method according to claim 39, ~~further comprising recovering the liquid disposed on the substrate,~~ wherein the magnitude of the velocity of movement of the substrate is decreased when the substrate is moved in a predetermined direction ~~in which a liquid recovery force is weak~~ as compared with when the substrate is moved in a direction different from the predetermined direction.

42-48. (Canceled)

49. (Currently Amended) A method for producing a device, ~~comprising using the exposure apparatus as defined in claim 14,~~ comprising:

exposing a substrate with the exposure apparatus of claim 14; and

processing the substrate to form the device.

50. (Currently Amended) A method for producing a device, ~~comprising using the exposure apparatus as defined in claim 16,~~ comprising:

exposing a substrate with the exposure apparatus of claim 16; and

processing the substrate to form the device.

51-53. (Canceled)

54. (Currently Amended) A method for producing a device, ~~comprising using the exposure method as defined in claim 39, comprising:~~

exposing a substrate by the exposure method of claim 39; and

processing the substrate to form the device.

55. (New) The exposure apparatus according to claim 14, wherein the liquid immersion area formed on the substrate stage includes a liquid immersion area on the substrate held on the substrate stage.

56. (New) The exposure apparatus according to claim 14, wherein when the distance between the first position and the second position is not less than a predetermined distance, the magnitude of the velocity of movement of the substrate stage is decreased such that the liquid is prevented from leaking from the liquid immersion area.

57. (New) The exposure apparatus according to claim 16, wherein when the substrate stage is moved in a predetermined direction, the magnitude of the velocity of movement of the substrate stage is decreased such that the liquid is prevented from leaking from the liquid immersion area.

58. (New) The exposure method according to claim 39, wherein the magnitude of the velocity of movement of the substrate is decreased such that the liquid is prevented from leaking from a liquid immersion area formed on the substrate.

59. (New) A method for producing a device, comprising:  
exposing a substrate with the exposure apparatus of claim 15; and  
processing the substrate to form the device.

60. (New) A method for producing a device, comprising:  
exposing a substrate with the exposure apparatus of claim 17; and  
processing the substrate to form the device.

61. (New) A method for producing a device, comprising:

exposing a substrate with the exposure apparatus of claim 56; and  
processing the substrate to form the device.

62. (New) A method for producing a device, comprising:  
exposing a substrate with the exposure apparatus of claim 57; and  
processing the substrate to form the device.
63. (New) A method for producing a device, comprising:  
exposing a substrate by the exposure method of claim 40; and  
processing the substrate to form the device.
64. (New) A method for producing a device, comprising:  
exposing a substrate by the exposure method of claim 41; and  
processing the substrate to form the device.
65. (New) A method for producing a device, comprising:  
exposing a substrate by the exposure method of claim 58; and  
processing the substrate to form the device.